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	Application No.	Applicant(s)
Notice of Allowability	10/668,375	LUDWIG ET AL.
	Examiner	Art Unit
	Roberts Culbert	1763
The MAILING DATE of this communication appears on the cover sheet with the correspondence address All claims being allowable, PROSECUTION ON THE MERITS IS (OR REMAINS) CLOSED in this application. If not included herewith (or previously mailed), a Notice of Allowance (PTOL-85) or other appropriate communication will be mailed in due course. THIS NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RIGHTS. This application is subject to withdrawal from issue at the initiative of the Office or upon petition by the applicant. See 37 CFR 1.313 and MPEP 1308.		
1. This communication is responsive to the amendment filed 1/20/06.		
2. The allowed claim(s) is/are <u>1-5,7,9,11-13 and 18-25</u> .		
 3. Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f). a) All b) Some* c) None of the: 1. Certified copies of the priority documents have been received. 		
2. Certified copies of the priority documents have been received in Application No		
3. Copies of the certified copies of the priority documents have been received in this national stage application from the		
International Bureau (PCT Rule 17.2(a)).		
* Certified copies not received:		
Applicant has THREE MONTHS FROM THE "MAILING DATE" of this communication to file a reply complying with the requirements noted below. Failure to timely comply will result in ABANDONMENT of this application. THIS THREE-MONTH PERIOD IS NOT EXTENDABLE.		
4. A SUBSTITUTE OATH OR DECLARATION must be submitted. Note the attached EXAMINER'S AMENDMENT or NOTICE OF INFORMAL PATENT APPLICATION (PTO-152) which gives reason(s) why the oath or declaration is deficient.		
5. CORRECTED DRAWINGS (as "replacement sheets") must be submitted.		
(a) ☐ including changes required by the Notice of Draftsperson's Patent Drawing Review (PTO-948) attached		
1) 🗌 hereto or 2) 🔲 to Paper No./Mail Date		
(b) ☐ including changes required by the attached Examiner's Amendment / Comment or in the Office action of Paper No./Mail Date		
Identifying indicia such as the application number (see 37 CFR 1.84(c)) should be written on the drawings in the front (not the back) of each sheet. Replacement sheet(s) should be labeled as such in the header according to 37 CFR 1.121(d).		
6. DEPOSIT OF and/or INFORMATION about the deposit of BIOLOGICAL MATERIAL must be submitted. Note the attached Examiner's comment regarding REQUIREMENT FOR THE DEPOSIT OF BIOLOGICAL MATERIAL.		
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Attachment(s)	5 D Negovici () 18	4 (4) (7 (770 (50)
1. Notice of References Cited (PTO-892)	<u> </u>	atent Application (PTO-152)
2. Notice of Draftperson's Patent Drawing Review (PTO-948)	6. Interview Summary Paper No./Mail Dat	e
3. Information Disclosure Statements (PTO-1449 or PTO/SB/0 Paper No./Mail Date		
4. Examiner's Comment Regarding Requirement for Deposit of Biological Material		nt of Reasons for Allowance
	9. Other	•
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Allowable Subject Matter

Claims 1-5, 7, 9, 11-13 and 18-25 are allowed.

The following is an examiner's statement of reasons for allowance: The prior art of record fails to teach or render obvious a method of repairing quartz defects on alternating phase shift masks, for repairing one and the same defect, the method comprising: performing defect repair method steps substantially based on etching processes; and performing defect repair method steps substantially based on mechanical processes thereafter, and wherein the step of performing repair method steps substantially based on etching processes includes processing the defect in a central region of the defect to completely remove the defect in the central region and processing the defect in an edge region of the defect to partially remove the defect in the edge region, wherein in the edge region in relation to the original height of the defect, between 20% and 50% of the defect is not removed prior to the step of performing defect repair method steps substantially based on mechanical processes. Takaoka et al. teach a method for repairing quartz defects on alternating phase shift masks, comprising: performing defect repair method steps substantially based on etching processes (focused ion beam) and performing defect repair method steps substantially based on mechanical processes thereafter. Verbeek et al. teaches that nanomachining methods may be used to successfully repair a partially repaired defect that has been left after conventional methods such as laser and focused ion beam.

Further, the prior art fails to teach a method for repairing quartz defects on alternating phase shift masks comprising: etching away an inner portion of a quartz defect on an alternating phase shift mask completely; etching away an edge region of the quartz defect to remove between 30% and 80% of the edge region; and mechanically removing the remaining 20% to 70% of the edge region of the quartz defect. Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

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Conclusion

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Any inquiry concerning this communication or earlier communications from the examiner should

be directed to Roberts Culbert whose telephone number is (571) 272-1433. The examiner can normally

be reached on Monday-Friday (8:30-5:00).

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor,

Parviz Hassanzadeh can be reached on (571) 272-1435. The fax phone number for the organization

where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application

Information Retrieval (PAIR) system. Status information for published applications may be obtained from

either Private PAIR or Public PAIR. Status information for unpublished applications is available through

Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should

you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC)

at 866-217-9197 (toll-free).

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R. Culbert Examiner

Art Unit 1763

Parviz Hassanzadeh

Supervisory Patent Examiner

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